

L Numb r	Hits	S arch T xt	DB	Tim stamp
-	2404	(430/311).CCLS.	USPAT; US-P PUB; EPO; JPO; DERWENT	2003/09/17 14:09
-	6	((430/311).CCLS.) and ((acid with diffus\$4 same (distort\$4 or footing or scalloping))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 15:48
-	35	((430/311).CCLS.) and (bi\$layer\$3 with (resist or photoresist))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/17 11:03
-	6	430/312 and ((acid with diffus\$4) same (distort\$4 or footing or scalloping))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 16:00
-	5	430/322 and ((acid with diffus\$4) same (distort\$4 or footing or scalloping))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 16:00
-	2467	430/322	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 16:03
-	2211	430/312	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/17 10:52
-	64	430/312 and (bi\$layer\$3 with (resist or photoresist))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/16 17:31
-	3581	430/313	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/17 11:03
-	231	430/313 and (CAR or (chemical\$4 near amplif\$6))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/17 11:08
-	10801	((resist or photoresist) and ((bi\$layer or bi\$level) or ((first and second) adj (layer or resist)))) and (thick\$4 and thin)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/17 12:07
-	7398	((resist or photoresist) and ((bi\$layer or bi\$level) or ((first and second) adj (layer or resist)))) and (thick\$4 same thin)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/17 12:07
-	91	((r sist r ph t r sist) and ((bi\$lay r r bi\$l v l) r ((first and s cond) adj (lay r or r sist)))) and (thick\$4 sam thin)) and ((t p adj surface) sam (imag\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/17 12:08

-	7096	((bi\$lay r r bi\$I v l or multi\$I v l) or (first and s c nd) or (t p and bott m)) n ar1 (r sist or phot r sist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/17 14:11
-	3141	((bi\$lay r r bi\$lev l or multi\$lev l) r (first and s c nd) r (top and b tt m)) n ar1 (resist or photoresist)) and (thick\$4 and thin\$4)	USPAT; US-P PUB; EPO; JPO; DERWENT	2003/09/17 14:13
-	100	((bi\$layer or bi\$level or multi\$level) or (first and second) or (top and bottom)) near1 (resist or photoresist)) and (thick\$4 and thin\$4)) and (surface near imag\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/17 15:10
-	136	((bi\$layer or bi\$level or multi\$level) or (first and second) or (top and bottom)) near1 (resist or photoresist)) and (surface near imag\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/17 15:31